

Independent Claim 1

1. A process for fabricating a product using a plasma source, said process comprising the steps of subjecting a substrate to entities, at least one of said entities emanating from a gaseous discharge excited by a high frequency field from an inductive coupling structure in which a phase portion and an anti -phase portion of capacitive currents coupled from the inductive coupling structure are selectively balanced;

wherein said inductive coupling structure is adjusted using a wave adjustment circuit, said wave adjustment circuit adjusting the phase portion and the anti -phase portion of the capacitively coupled currents.

Figure 2A Of The '221 Patent

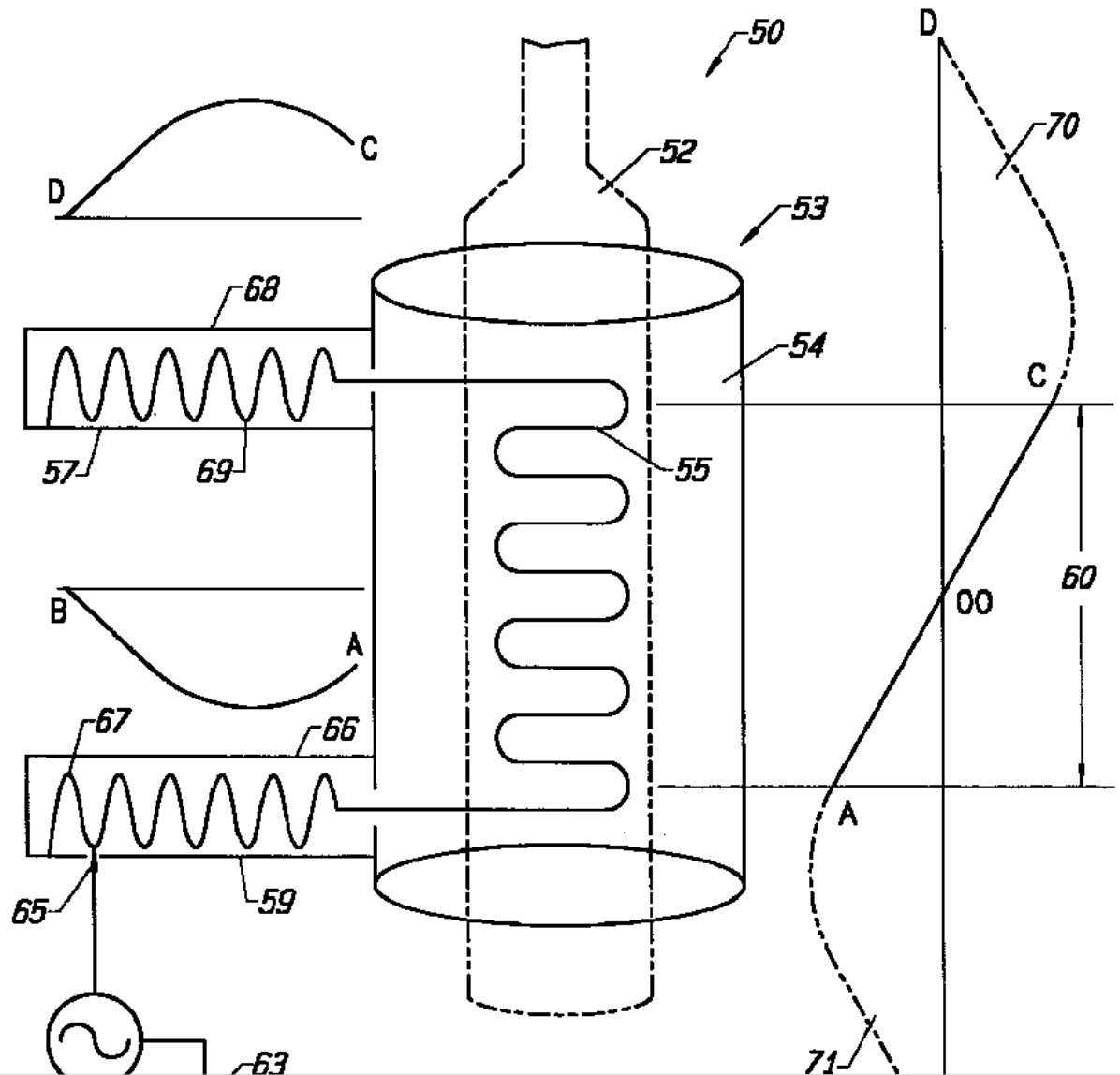


Figure 4 Of The '221 Patent

